

PATENT ABSTRACTS OF JAPAN

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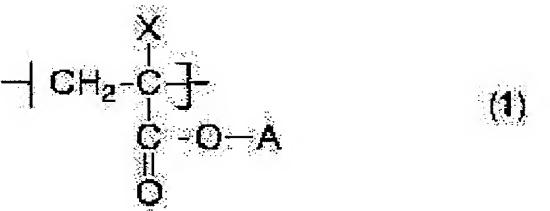
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(54) POSITIVE TYPE RADIATION SENSITIVE COMPOSITION

(57)Abstract:

PROBLEM TO BE SOLVED: To obtain a high sensitivity positive type radiation sensitive composition having such resolution as to attain sub-quarter-micron patterning.

SOLUTION: The positive type radiation sensitive composition contains a polymer containing a structural unit of formula 1 (where X is fluorine-containing alkyl; and A is a monovalent organic group having tertiary carbon combined to oxygen and containing an aromatic ring) and an acid generating agent which generates an acid when irradiated.



LEGAL STATUS

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